

| L Number | Hits | Search Text  | DB  | Time stamp       |
|----------|------|--|---|------------------|
| 1        | 59   | ((((silicon near (dioxide oxide)) siO siO2 siO?sub.2) same (layer coating)) and (root near mean near square near surface near roughness))  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT | 2003/11/21 15:40 |
| 2        | 18   | (428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and (surface near roughness))) and (428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and haze)) and (428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and (humidity rh!)))  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT | 2003/11/21 15:41 |
| 3        | 76   | ((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and (root near mean near square near surface near roughness))   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT | 2003/11/21 15:41 |
| 4        | 12   | ((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((relative near humifity) rh!)   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT | 2003/11/21 15:41 |
| 5        | 33   | ((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((humidity) rh!)   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT | 2003/11/21 15:41 |
| 6        | 72   | 428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) same haze)   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT | 2003/11/21 15:42 |
| 7        | 99   | ((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2)) and (root near mean near square near surface near roughness))  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT | 2003/11/21 15:42 |
| 8        | 25   | (((((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and (surface near roughness) ) and (vapor near (deposition deposited deposit depositing))) and (alkylchlorosilane dimethyldichlorosilane trimethylchlorosilane CH32Cl2Si CH32SiCl2 CH3Cl3Si ch3sicl3 (ch?sub.3 near ?sub.2 near cl?sub.2 near Si) (ch?sub.3 near ?sub.2 near si near cl?sub.2) (ch?sub.3 near cl?sub.3 near si) (ch?sub.3 near si near cl?sub.3))) | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT | 2003/11/21 15:43 |
| 9        | 129  | ((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) and (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and (surface near roughness) ) and (vapor near (deposition deposited deposit depositing)))  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT | 2003/11/21 15:43 |
| 10       | 59   | ((silicon near (dioxide oxide)) siO siO2 siO?sub.2) same (layer coating)) and (root near mean near square near surface near roughness))  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT | 2003/11/21 15:43 |
| 11       | 76   | ((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and (root near mean near square near surface near roughness))   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT | 2003/11/21 15:44 |
| 12       | 18   | (428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and (surface near roughness))) and (428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and haze)) and (428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and (humidity rh!)))  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT | 2003/11/21 15:44 |
| 13       | 12   | ((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((relative near humifity) rh!)   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT | 2003/11/21 15:44 |
| 14       | 33   | ((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((humidity) rh!)   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT | 2003/11/21 15:44 |

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| 15 | 72  | 428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) same haze)   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT | 2003/11/21 15:44 |
| 16 | 99  | (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2)) and (root near mean near square near surface near roughness)  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT | 2003/11/21 15:44 |
| 17 | 25  | ((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (surface near roughness) ) and (vapor near (deposition deposited deposit depositing))) and (alkylchlorosilane dimethyldichlorosilane trimethylchlorosilane CH32Cl2Si CH32SiCl2 CH3cl3Si ch3sicl3 (ch?sub.3 near ?sub.2 near cl?sub.2 near Si) (ch?sub.3 near ?sub.2 near si near cl?sub.2) (ch?sub.3 near cl?sub.3 near si) (ch?sub.3 near si near cl?sub.3)) | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT | 2003/11/21 15:45 |
| 18 | 129 | ((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) and (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (surface near roughness) ) and (vapor near (deposition deposited deposit depositing)))  | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT | 2003/11/21 15:45 |

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| 19 | 34 | <p> ((((silicon near (dioxide oxide)) siO siO2 siO?sub.2) same (layer coating)) and (root near mean near square near surface near roughness) ) ((428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and (surface near roughness))) and (428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and haze)) and (428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and (humidity rh))) ) (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and (root near mean near square near surface near roughness) ) (((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((relative near humifity) rh!) ) (((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((humidity) rh!) ) (428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) same haze) ) (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) ) and (root near mean near square near surface near roughness) ) (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and (surface near roughness) ) and (vapor near (deposition deposited deposit depositing))) and (alkylchlorosilane dimethyldichlorosilane trimethylchlorosilane CH32Cl2Si CH32SiCl2 CH3cl3Si ch3sicl3 (ch?sub.3 near ?sub.2 near cl?sub.2 near Si) (ch?sub.3 near ?sub.2 near si near cl?sub.2) (ch?sub.3 near cl?sub.3 near si) (ch?sub.3 near si near cl?sub.3)) ) (((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) and (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and (surface near roughness) ) and (vapor near (deposition deposited deposit depositing))) ) (((silicon near (dioxide oxide)) siO siO2 siO?sub.2) same (layer coating)) and (root near mean near square near surface near roughness) ) (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and (root near mean near square near surface near roughness) ) ((428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and (surface near roughness))) and (428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and haze)) and (428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and (humidity rh))) ) (((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((relative near humifity) rh!) ) (((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((humidity) rh!) ) (428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) same haze) ) (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) ) and (root near mean near square near surface near roughness) ) (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and (surface near roughness) ) and (vapor near (deposition deposited deposit depositing))) and (alkylchlorosilane dimethyldichlorosilane trimethylchlorosilane CH32Cl2Si CH32SiCl2 CH3cl3Si ch3sicl3 (ch?sub.3 near ?sub.2 near cl?sub.2 near Si) (ch?sub.3 near ?sub.2 near si near cl?sub.2) (ch?sub.3 near cl?sub.3 near si) (ch?sub.3 near si near cl?sub.3)) ) (((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) and (((silicon near (dioxide oxide)) silica siO siO2 siO?sub.2) same (layer coating)) and (surface near roughness) ) and (vapor near (deposition deposited deposit depositing))) ) and @pd&gt;20030616 </p> | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT | 2003/11/21 15:45 |
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